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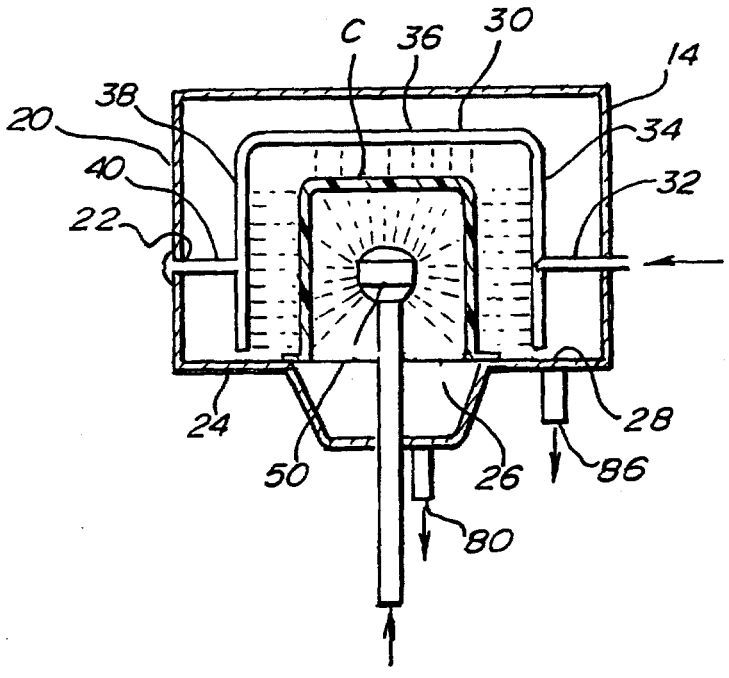
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(54) Title: WAFER CONTAINER WASHING APPARATUS



(57) Abstract: A wafer carrier (10) cleaner which comprises a base (24) having a first aperture (16) and a second aperture (26). The wafer cleaner (10) includes a first sprayer (30), and a second sprayer (50), with the first sprayer (30) configured to direct a series of cleaning fluids about the exterior surface of a wafer carrier (C), and the second sprayer (50) configured to direct a series of cleaning fluids about the interior surface of a wafer carrier (C). The expended fluids used to clean the exterior surface of the wafer carrier (C) are directed through the first aperture (16) and into a first fluidic circuit, and the expended fluids used to clean the interior surface of the wafer carrier (C) are directed through the second aperture (26) and into a second fluidic circuit. The provision of dedicated fluidic circuits for the exterior and interior cleaning fluids reduces cross contamination.

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